

Korean International Semiconductor Conference & Exhibition on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[ThC1] Advanced Metrology & inspection, Process diagnostics & control, and Yield	
management V	
Session Date	November 13 (Thu.), 2025
Session Time	09:00-10:20
Session Room	Room C (Grand Ballroom 3, 2F)

[ThC1-1] [Invited] 09:00-09:20

High-/Low-Pressure Swing Annealing for Uniform Curing of High-Aspect-Ratio TiN Electrodes in DRAM Capacitors

Won Jun Jang (Sungkyunkwan Univ. and Wonik IPS, Korea), Won Sik Ahn (Wonik IPS, Korea), Woo Hui Lee, and Hyoungsub Kim (Sungkyunkwan Univ., Korea)

[ThC1-2] [Invited] 09:20-09:50

A New Approach to High-Throughput Defect Review of Unpatterned Wafers for Leading Edge Nodes

Ali Ozhan Altun (UNISERS AG, Switzerland)

[ThC1-3] [Invited] 09:50-10:20

Advanced Technique for Analysis of Defect States in Future 3D Semiconductor Devices Hagyoul Bae (Jeonbuk Nat'l Univ., Korea)